

CHROMIUM SINTERED BODY, METHOD FOR PRODUCING
CHROMIUM SINTERED BODY, SPUTTERING TARGET, AND
METHOD FOR PRODUCING SUBSTRATE WITH CHROMIUM
FILM

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ABSTRACT

[Problems] There are provided a chromium sintered body that has a low oxygen content and that enables the production of a sputtering target with which thickness uniformity of a chromium film can be improved when
10 the chromium film is formed by a sputtering method, a method for producing the chromium sintered body, a sputtering target, and a method for producing a substrate with a chromium film.

[Solution] A chromium sintered body includes grains. The grains have an average KAM value of 2° or less, and the grains have an average grain
15 size of more than $150\ \mu\text{m}$ and $400\ \mu\text{m}$ or less.

[Fig. 1]